

## PATENT APPLICATION

## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of

Docket No: Q56799

Masami HATORI

Appln. No.: 09/533,678

Group Art Unit: 2828

Confirmation No.: 1082

Examiner: Tuan M. Nguyen

Filed: March 23, 2000

For: SEMICONDUCTOR LASER MODULE AND METHOD FOR FORMING

SEMICONDUCTOR LASER MODULE

AMENDMENT UNDER 37 C.F.R. § 1.111

RECEIVED

Commissioner for Patents Washington, D.C. 20231

APR 1 6 2003

**Technology Center 2600** 

Sir:

In response to the Office Action dated January 15, 2003, please amend the aboveidentified application as follows:

## IN THE CLAIMS:

## Please add the following new claims:

16 (New). The semiconductor laser module of claim 2, wherein the predetermined angle is defined as  $\theta$ , and wherein

 $d = Ltan\theta$ ,

where d is a depth of domain inversion and L is a length of a domain inversion region.

17 (New). The semiconductor laser module of claim 2, wherein the predetermined angle is defined as  $\theta$ , and wherein

AMENDMENT UNDER 37 C.F.R. § 1.111 U.S. Appln. No. 09/533,678

 $d = Ltan\theta + C$ ,

where d is a depth of domain inversion and L is a length of a domain inversion region, and C is a spreading constant for domain inversion.

a' d

18 (New). The semiconductor laser module of claim 16, wherein a width ratio of a domain inversion region to a domain non-inversion region is 1:1.

19 (New). The method according to claim 12, wherein a top surface of the substrate is disposed with a first electrode and a bottom surface of the substrate is disposed with a second electrode, wherein the first and second electrodes are offset from each other such that the electrodes do not overlap, said electrodes used to form the domain inversion regions.